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PATENT (q-b-07)

Reply Under 37 CFR 1.116 Expedited Procedure Technology Center 1700

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:

Young Sun Hwang et al.

Serial No.:

10/719,083

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Filed:

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Title:

METHODS FOR FORMING

FINE PHOTORESIST

**PATTERNS** 

Group Art Unit: 1765

1705

Examiner:

Patricia Ann George

Attorney Docket No.: 30205/39513

/ Sandip H. Patel /

Sandip H. Patel (Reg. No. 43,848)

I hereby certify that this paper (along with

any paper referred to as being attached or enclosed) is being transmitted via EFS-

Web to the U.S. Patent and Trademark

Attorney for Applicants

Office on July 19, 2007.

## RESPONSE TO FINAL OFFICIAL ACTION

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Dear Sir:

This paper is being submitted in response to the final official action dated April 19, 2007.

Remarks begin on page 2 of this paper.

A complete listing of the existing claims is not required (or presented herein) because no changes are being made to the claims, no claims are being canceled, and no claims are being added. See 37 CFR § 1.121(c).